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STATEMENT BY APPLICANT**

(Use several sheets if necessary)

ATTY. DOCKET NO.

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APPLICANT

Y. LI, et al

FILING DATE

July 28, 1998

GROUP

1763

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	ABSTRACT	
							YES	NO
<i>72</i>	7	2 0 1 8 3 1	8/95	Japan			XX	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>72</i>		Y. Li, et al "Plasma-density Control in the Magnetron-type RF Plasma", Plasma Sources Sci. Technology 5 (1996) pp. 241-244.
		Y. Li, et al "Plasma Structure in a Modified Magnetron-typed RF Discharge", Proceedings of the 13 th Symposium on Plasma Processing, Tokyo, Japan, 1996, pp. 53-56.
		Y. Li, et al "Production of 1-m-Size Uniform Plasma by Modified Magnetron-Typed RF Discharge", SPSM-10, Tokyo, 1997.
		Y. Li, et al, "Electron Temperature Control in Large-Diameter Radio-Frequency Plasma", Proceedings of the 3 rd Asia-Pacific Conference on Plasma Science & Technology, Tokyo, Japan, 1996, pp. 435-439.
		S. Wickramanayaka, et al, "Variation of Radial Plasma Density Profile with the Excitation Frequency in a Magnetron-type Plasma", J. Appl. Phys. Vol. 37, 1998, pp. 2035-2038.
		N. Sato, et a; "Sputtering Control in a Modified RF Plasma", Proceedings of the International Workshop on Basic Aspects of Nonequilibrium Plasmas Interacting with Surfaces, Shirahama, Japan, 1997, pp. 27-28.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation is considered, draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

(Form PTO-1449 [6-4])